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IDS
K. Jones
10/30/01

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Atty. Docket

RENE MONSHOUWER ET AL

NL 000770

Serial No.

11017 U.S. PTO
09/940819
08/28/01

Filed: CONCURRENTLY

METHOD OF MEASURING ALIGNMENT OF A SUBSTRATE WITH RESPECT TO A
REFERENCE ALIGNMENT MARK

Commissioner for Patents
Washington, D.C. 20231

AUTHORIZATION PURSUANT TO 37 CFR §1.136(a)(3)
AND TO CHARGE DEPOSIT ACCOUNT

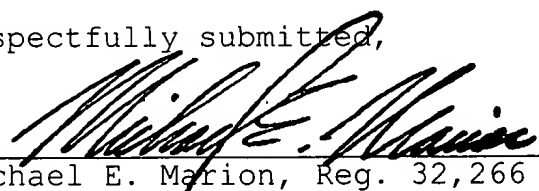
Sir:

The Commissioner is hereby requested and authorized to treat any concurrent or future reply in this application requiring a petition for extension of time for its timely submission, as incorporating a petition for extension of time for the appropriate length of time.

Please charge any additional fees which may now or in the future be required in this application, including extension of time fees, but excluding the issue fee unless explicitly requested to do so, and credit any overpayment, to Deposit Account No. 14-1270.

Respectfully submitted,

By


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INFORMATION DISCLOSURE STATEMENT TRANSMITTAL

To Commissioner For Patents

Enclosed herewith is a Form PTO-1449, required copies of documents listed thereon, and a concise explanation of their relevance is described below or enclosed herewith per 37 CFR 1.97.

Application Number

Filing Date

CONCURRENTLY

First Named Inventor

Rene Monshouwer
et al

Group Art Unit

Examiner Name

Attorney Docket Number

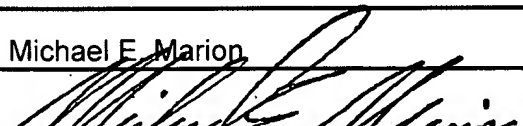
NI 000770

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08/28/01

These documents may be relevant in that they have been:

- ☒ considered in drafting the specification of the above-referenced application;
- ☒ cited in the specification of the above-referenced application;
- ☐ previously submitted or cited in U.S. patent application(s) _____ which are relied on for an earlier effective filing date under 35 U.S.C. 120 (no copy required); or
- ☐ cited as an "X" or "Y" document in a foreign Patent Office search report on a foreign counterpart application, a copy of which report is also enclosed;
☐ I hereby certify that these documents were first cited in any communication with a foreign Patent Office for a counterpart foreign application not more than three (3) months ago;
- ☐ Otherwise a concise explanation of the relevance of each document is append hereto.
☐ I hereby certify that not one of these documents was cited in any communication with a foreign Patent Office nor was any known to any individual designated in §1.56(c) more than three (3) months ago.

SIGNATURE OF APPLICANT, ATTORNEY, OR AGENT REQUIRED

Name (Print Type)	Michael E. Marion	Registration No. (Attorney/Agent)	32,266
Signature		Date	August 28, 2001

Form PTO-1449 U.S. DEPARTMENT OF COMMERCE (REV. 7-80) PATENT AND TRADEMARK OFFICE		DOCKET NO. N1 000770		Serial No.		j1017 U.S. PTO 09/940819	
INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)		Applicant Rene Monshouwer et al				Group	
		Filing Date Concurrently					
U.S. PATENT DOCUMENTS							
Ex. Int.	Document Number	Date	Name	Class	Sub- class	Filing Date If Approp.	
	AA	5 1 4 4 3 6 3	9/1/92	Wittekoek et al	355	53	1/24/91
	AB	4 5 4 0 2 7 7	9/10/85	Mayer et al	355	53	6/24/83
	AC	4 7 3 7 8 2 3	4/12/88	Bouwer et al	355	53	10/14/86
	AD	5 0 2 6 1 6 6	6/25/91	Van der Werf	356	401	10/1/84
	AE	5 1 9 1 2 0 0	3/2/93	Van der Werf	250	201	12/16/91
	AF	4 3 5 6 3 9 2	10/26/82	Wittekoek et al	250	201	6/11/80
	AG	4 8 6 1 1 6 2	8/29/89	Ina et al	356	401	11/15/88
	AH	5 4 1 4 5 1 4	5/9/95	Smith et al	356	363	6/1/93
	AI	4 7 7 8 2 7 5	10/18/88	Van den Brink	356	401	9/24/86
	AJ	4 2 5 1 1 6 0	2/17/81	Bouwhuis et al	356	401	7/13/78
	AK	5 2 4 3 1 9 5	9/7/93	Nishi	250	548	12/29/92
FOREIGN PATENT DOCUMENTS							
	Document Number	Date	Country	Class	Sub- Class	Trans.	
						Yes	No
AL	0 4 9 8 4 9 9 A 1	8/12/92	Europe			X	
AM	9 8 3 9 6 8 9 A 1	9/11/98	World			X	
OTHER (Including Author, Title, Date, Pertinent Pages, Etc.)							
AN	"Submicrometer Lithographic Alignment and Overlay Strategies", by Saleem H. Zaidi et al, SPIE Vol. 1343, 1990, pages 245-255.						
AO	"Submicron 1:1 Optical Lighography", by David A. Markle, Semiconductor International May 1986.						
Examiner				Date Considered			